

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method for examination of nonuniformity defects of ~~patterns in a photomask pattern for manufacturing an image device, the photomask pattern including a repetitive pattern having a plurality of unit patterns arranged according to a regularity, the method comprising:~~  
~~comprises~~ emitting light to the plurality of unit patterns to generate diffraction light at an edge portion of the repetitive pattern; an examination object whose surface is provided with a repeating pattern in which unit patterns are arrayed in a regular fashion, photodetecting transmitted light or reflected light from the examination object, and observing the detected photodetection data to detect nonuniformity defects that have occurred in said repeating pattern, wherein  
photodetecting the diffraction light to produce a photodetection data; and  
observing the photodetection data to determine nonuniformity defects, the nonuniformity defects occurring in the plurality of unit patterns according to another regularity,  
wherein the light comprises a monochromatic laser light having a wavelength of 500 to 570 nm, and  
the nonuniformity defects are determined by identifying a disarrangement in the regularity of the photodetection data.  
~~the method for examination of nonuniformity defects of patterns further comprises selecting and extracting light of one or a plurality of desired wavelength bands from light of a plurality of wavelength bands, and detecting nonuniformity defects of said repeating pattern by using the light of the selected and extracted wavelength bands.~~

2.-3. (Canceled)

4. (Currently Amended) A device for examination of nonuniformity defects in a photomask pattern~~of patterns~~ for manufacturing an image device, the photomask pattern including a repetitive pattern having a plurality of unit patterns arranged according to a regularity, the device comprising:  
~~having~~ \_\_\_\_\_ a light source for emitting monochromatic laser light having a wavelength of 500 to 570 nm to the plurality of unit patterns to generate diffraction light at an edge portion of the repetitive pattern;~~to an examination object whose surface is provided with a repeating pattern in which unit patterns are arrayed in a regular fashion, and~~  
 \_\_\_\_\_ a photodetector for photodetecting the diffraction light to produce a photodetection data ~~transmitted light or reflected light from said examination object and converting the light into photodetection data, so that~~ that the nonuniformity defects, which occur in the plurality of unit patterns according to another regularity, are determined by identifying a disarrangement in the regularity of the photodetection data is observed to detect nonuniformity defects that have occurred in said repeating pattern, wherein  
 \_\_\_\_\_ ~~the device for examination of nonuniformity defects of patterns further has selection and extraction means for selecting and extracting light of one or a plurality of desired wavelength bands from the light of a plurality of wavelength bands, so that nonuniformity defects of said repeating pattern are detected using the light of the selected and extracted wavelength bands.~~

5.-8. (Canceled)

9. (Currently Amended) ~~The device for examination of nonuniformity defects of patterns~~ according to claim 4, wherein said selection and extraction means is provided with light source comprises a plurality of monochromatic light sources for individually emitting light of a desired wavelength band ~~selected from the light of a plurality of wavelength bands,~~

~~and is configured to allow the light emission operation of the monochromatic light sources to be switched.~~

10.-20. (Canceled)